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JC14 Rec'd PCT/PTO 0 6 MAY 2005

Date of Deposit:: May 6, 2005

Case No. 9905/25

### UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)	
ASPAR et al.	)	
Serial No.: Not Yet Assigned	)	Examiner: Not Yet Assigned
Filing Date: Herewith	)	Group Art Unit:
or: METHOD FOR FORMING A BRITTLE ZONE IN A SUBSTRATE BY CO-IMPI ANTATION	)	Not Yet Assigned

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Dear Sir:

In accordance with the duty of disclosure under 37 C.F.R. §1.56 and §§1.97-1.98, and more particularly in accordance with 37 C.F.R. §1.97(b), Applicants hereby cite the following references:

No.	Date of Publication	Patentee/Applicant/Assignee
US 6,150,239	11/21/2000	Goesele et al.
US 6,020,252	02/01/2000	Aspar et al.
US 5,374,564	12/20/1994	Bruel
FR 2 774 510 A1	08/06/1999	France
FR 2 773 261 A1	07/02/1999	France
FR 2 767 416 A1	02/19/1999	France
FR 2 748 851 A1	11/21/1997	France
FR 2 748 850 A1	11/21/1997	France
FR 2 681 472 A1	03/19/1993	France
WO 00/63965	10/26/2000	PCT
WO 99/39378	08/05/1999	PCT
EP 0786801 A1	07/30/1997	EPO
EP 0801419 A1	10/15/1997	EPO
11-87668	03/30/1999	Japan

Agarwal et al., Efficient Production of Silicon-on-Insulator Films by Co-Implantation of He+ with H+. 1998 American Institute of Physics, Volume 72, number 9, March 2, 1998, pp. 1086-1088.

10/534199

Attorney Docket No., 9905/25 (BIF023239/DM)

JC14 Rec'd PCT/FTO 0 6 MAY 2005

For the Examiner's convenience, Applicants are enclosing Form PTO-1449 (one sheet), and as each of the listed references is in English, no further commentary is believed to be necessary, 37 C.F.R §1.98(a)(3). Applicant respectfully requests the Examiner's consideration of the above references and entry thereof into the record of this application.

Also enclosed is a copy of the International Search Report issued on March 19, 2004 for corresponding PCT Application No. PCT/FR03/03256 of the above-identified application.

By submitting this Statement, Applicants are attempting to fully comply with the duty of candor and good faith mandated by 37 C.F.R. §1.56. As such, this Statement is not intended to constitute an admission that any of the enclosed references, or other information referred to therein, constitutes "prior art" or is otherwise "material to patentability," as that phrase is defined in 37 C.F.R. §1.56(a).

Applicants have calculated no fee to be due in connection with the filing of this Statement. However, the Director is authorized to charge any fee deficiency associated with the filing of this Statement to a deposit account, as authorized in the Transmittal accompanying this Statement.

Respectfully submitted,

May 6, 2005

Jasper W. Dockrey (Reg. No. 33,868) Attorney for Applicants

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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. BS: 1005

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FORM PTO-1449	SERIAL NO.	CASE NO.
	Not Yet Assigned	9905/25
		(BIF023239/DM)
LIST OF PATENTS AND PUBLICATIONS FOR	FILING DATE	GROUP ART UNIT
APPLICANT'S INFORMATION DISCLOSURE	Herewith	Not Yet Assigned
STATEMENT		
	APPLICANTS: ASPAR et al.	

## REFERENCE DESIGNATION

#### U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER Number-Kind Code (if known)	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
/BS/	A1	6,150,239	11/21/2000	Goesele et al.		
/BS/	A2	6,020,252	02/01/2000	Aspar et al.		
/BS/	A3	5,374,564	12/20/1994	Bruel		

#### FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER Number-Kind Code (if known)	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
/BS/	A4	FR 2 774 510 A1	08/06/1999	France		
/BS/	A5	FR 2 773 261 A1	07/02/1999	France		
/BS/	<b>A</b> 6	FR 2 767 416 A1	02/19/1999	France		
/BS/	A7	FR 2 748 851 A1	11/21/1997	France		
/BS/	A8	FR 2 748 850 A1	11/21/1997	France		
/BS/	A9	FR 2 681 472 A1	03/19/1993	France		
/BS/	A10	WO 00/63965	10/26/2000	PCT		
/BS/	A11	WO 99/39378	08/05/1999	PCT		
/BS/	A12	EP 0786801 A1	07/30/1997	EPO		
/BS/	A13	EP 0801419 A1	10/15/1997	EPO		
/BS/	A14	11-87668	03/30/1999	Japan		Abstract

EXAMINER INITIAL		OTHER ART – NON PATENT LITERATURE DOCUMENTS nclude name of author, title of the article (when appropriate), title of the item (book, mazine, journal, serial, sposium, catalog, etc.), date page(s), volume-issue unumber(s), publisher, city and/or country where published.
/BS/	<b>A</b> 15	Agarwal et al., Efficient Production of Silicon-on-Insulator Films by Co-Implantation of He+ with H+, 1998 American Institute of Physics, Volume 72, number 9, March 2, 1998, pp. 1086-1088.

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EXAMINER	/Bradley Smith/	DATE CONSIDERED	02/16/2009

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.